

Atty. Dkt. No. AMAT/2592.C9/DSM/LOW K/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Application of:  
Gaillard, et al.

**Serial No.: 10/789,209**

**Confirmation No.: 9101**

**Filed: February 27, 2004**

For: Method of Decreasing the  
K Value in SiOC Layer  
Deposited by Chemical  
Vapor Deposition

**Group Art Unit: 2818**

**Examiner: David Nhu**

**MAIL STOP ISSUE FEE**  
**Commissioner for Patents**  
**P.O. Box 1450**  
**Alexandria, VA 22313-1450**

**Dear Sir:**

**CERTIFICATE OF MAILING**

**37 CFR 1.8**

I hereby certify that this correspondence is being deposited on 6/13, 2005 with the United States Postal Service as First Class Mail in an envelope addressed to: Mail Stop Issue Fee, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

6/3/05  
Date

**Signature**

### AMENDMENT AFTER ALLOWANCE

Following mailing of a Notice of Allowance on May 9, 2005, Applicants request entry of the following amendments. **Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper. **Remarks** begin on page 6 of this paper.